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(71) Applicant (for all designated States except US): **CABOT
MICROELECTRONICS CORPORATION** [US/US];
870 North Commons Drive, Aurora, IL 60504 (US).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **SCHROEDER,
David, J.** [US/US]; c/o Legal Department, Cabot Micro-
electronics, 870 North Commons Drive, Aurora, IL 60504
(US). **MOEGGENBORG, Kevin, J.** [US/US]; c/o Legal
Department, Cabot Microelectronics, 870 North Commons
Drive, Aurora, IL 60504 (US).

(74) Agent: **WESEMAN, Steven, D.**; Associate General
Counsel, Intellectual Property, Cabot Microelectronics
Corporation, 870 North Commons Drive, Aurora, IL
60504 (US).

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(54) Title: **CHEMICAL-MECHANICAL POLISHING COMPOSITION AND METHOD FOR USING THE SAME**

(57) Abstract: The invention provides a chemical-mechanical polishing composition comprising: (a) silica particles, (b) about 5×10^{-3} to about 10 millimoles per kilogram of at least one alkaline earth metal selected from the group consisting of calcium, strontium, barium, and mixtures thereof, based on the total weight of the polishing composition, (c) about 0.1 to about 15 wt.% of an oxidizing agent, and (d) a liquid carrier comprising water. The invention also provides a polishing composition, which optionally comprises an oxidizing agent, comprising about 5×10^{-3} to about 10 millimoles per kilogram of at least one alkaline earth metal selected from the group consisting of calcium, strontium, and mixtures thereof. The invention further provides methods for polishing a substrate using the aforementioned polishing compositions.

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